

Published on Web 09/08/2004

A Unique Reaction Pathway of Fluorine-Substituted Ethyl Groups on Cu(111): Successive α,α-Fluoride Elimination

Chao-Ming Chiang,*,† Deyi Lu,† Jia-Tze Huang,† Chi-Chau Hwang,† Chia-Chin Cho,†

Liang-Jen Fan,[‡] and Yaw-Wen Yang^{*,‡}

Department of Chemistry, Center for Nanoscience and Nanotechnology, National Sun Yat-Sen University, Kaohsiung, Taiwan 80424, and National Synchrotron Radiation Research Center (NSRRC), Hsinchu, Taiwan 30077 Received April 15, 2004; E-mail: cmc@mail.nsysu.edu.tw; yang@nsrrc.org.tw

Replacement of hydrogen with fluorine usually results in a marked change in the physical and chemical properties of fluorocarbons. Numerous studies have shown that fluorinated radicals and their metal complexes have structures and reactivities deviating from their hydrocarbon counterparts.^{1–3} Surface studies of adsorbed perfluoroalkyl moieties beyond C₁, in comparison, remain largely unexplored. Here we report a surface reaction study of the fluorinesubstituted ethyl groups on Cu(111) that displays novel reaction pathways driven by α -elimination, instead of β -elimination found commonly in hydrocarbons.

Temperature-programmed reaction/desorption (TPR/D) and reflection absorption infrared spectroscopy (RAIRS) were conducted in an in-house ultrahigh vacuum chamber. X-ray photoemission spectra (XPS) were acquired in the wide-range spherical grating monochromator beamline at NSRRC. The surface-bound perfluoroethyl moieties were prepared by the dissociative adsorption of $C_2F_5I.^4$

As illustrated in Figure 1 (left), following the adsorption of 0.6 L of C₂F₅I (98%, SynQuest) at 110 K, multiple-ion TPR/D survey shows four desorption states with peak maxima at 315, 350, 425, and 880 K, respectively. The 880 K state is featured by m/e 82(63-CuF) and 84(65CuF) with a peak height ratio matching the natural abundance of copper isotopes; hence, the substrate is etched through forming volatile copper fluoride.⁵ Here the origin of the fluorine atoms hints that some, if not all, of the C-F bonds in Cu-C₂F₅ must be ruptured. The 315 K state is primarily characterized by m/e 181(C₄F₇⁺), 131(C₃F₅⁺), 100(C₂F₄⁺), and 93(C₃F₃⁺). Their relative abundance agrees with the measured cracking pattern of CF₃-CF=CFCF₃(C₄F₈),⁶ inferring single F abstraction at the α -carbon in perfluoroethyl,⁷ Cu $^{-\alpha}$ CF₂CF₃ \rightarrow Cu=CFCF₃ + Cu-F, followed by a dimerization step.8 The 350 K desorption state can be understood in terms of product mixtures. First, the observation of m/e $100(C_2F_4^+)$ and $119(C_2F_5^+)$ may arise from desorption of C_2F_5 radicals.⁹ However, the lack of m/e 81(C₂F₃⁺) rules out a possible contribution from CF₂=CF₂(m/e 100), a direct result from β -F elimination. This clear preference to α -elimination, rather than β elimination, is rarely observable in hydrocarbon ($>C_1$) systems.¹⁰ Second, a featureless trace of m/e 169(C₃F₇⁺) ensures the absence of perfluorobutane (C₄F₁₀), and the concurrence of m/e 93(C₃F₃⁺), $143(C_4F_5^+)$, and $162(C_4F_6^+)$ signals is attributable to unsaturated C₄F₆ compounds. The above three fragments are also found in the pronounced 425 K desorption state, however, with different relative intensities. Logically, the intermediacy of Cu-C₂F₃ is invoked to account for the observed C₄F₆ recombinants at these temperatures; in other words, two C-F bonds must be selectively activated in the starting Cu-C₂F₅. The coverage-dependent study, shown in Figure 1 (right), manifests that at very low exposure the 425 K C_4F_6 is the sole fluorocarbon product. At high coverage, a crossover of



Figure 1. Left: Multiplex TPR/D spectra after the adsorption of 0.6 L of C_2F_5I on Cu(111) at 110 K. Right: The trend of m/e 93 and 131 signals shows change of C_4F_6 and C_4F_8 relative yields with increasing exposures.



Figure 2. TPR/D traces of m/e 93, 143, and 162, representing C₄F₆ evolution from (a) C₂F₅I, (b) C₄F₆ isomers, (c, top) CF₂=CFI, and (c, bottom) CF₃CCl₃ adsorbed on Cu(111) at 110 K. The exposures are kept low enough to focus on the 425 K pathway. (d) TPR/D profiles after exposing C₂F₅I to Cu(100), indicating C₄F₆ is not formed on this surface.

yield from C_4F_6 to C_4F_8 is noted, consistent with the requirement for more empty surface sites in the process of making the former species.

In Figure 2a, the TPR/D profiles of m/e 93, 143, and 162 resulting from $C_2F_5I/Cu(111)$ are compared with those (Figure 2b) from the individually adsorbed hexafluoro-2-butyne, -cyclobutene, and -1,3butadiene (C₄F₆ isomers, 98%, SynQuest). On the basis of the fragmentation ratios determined by our mass spectrometer, it is safe to assign the 425 K major product to 2-butyne and the 350 K species to cyclobutene. To further identify the postulated surface C₂F₃ intermediate, we used the readily available perfluorovinyl iodide (CF₂=CFI, 97%, Lancaster) as a direct route to form Cu-C₂F₃. As displayed in Figure 2c (top), traces of m/e 93, 143, and 162, characteristic of hexafluoro-2-butyne, are indeed observed, yet appear only at 425 K. Despite the essential difference between perfluoroethyl and perfluorovinyl, the outcome of the same end product at 425 K seems to suggest that perfluoroethyl undergoes sequential fluoride elimination from the α - and β -carbons to render perfluorovinyl, namely, $Cu - \alpha CF_2 CF_3 \rightarrow Cu = CF^{\beta} CF_3 \rightarrow Cu - CF =$ CF₂. But, the question remains: why is C₄-diene not observed, considering the fact that copper would promote coupling of Cu-CF=CF₂ (Ullman-type reaction)?¹¹ By losing two fluorine atoms from the α-carbon in Cu-CF₂CF₃, an alternative intermediate, trifluoroethylidyne (Cu=C-CF₃) certainly deserves attention. Because d'Itri and co-workers reported identification of the surface

[†] National Sun Yat-Sen University. [‡] National Synchrotron Radiation Research Center.

 \equiv C-CF₃ species formed upon adsorption and dechlorination of CCl_3CF_3 on a Pd/ γ -Al₂O₃ catalyst,⁷ TPR/D spectra were measured by exposing Cu(111) to CCl₃CF₃ (99%, Aldrich). The data shown in Figure 2c (bottom) also support the evolution of $CF_3C \equiv CCF_3$ at 425 K. In principle, the controversy about the reaction intermediacy can be resolved by direct surface spectroscopic methods. RAIR spectra taken after annealing C₂F₅I on Cu(111) showed dramatic changes at 400 K (near the onset of 2-butyne desorption), where only two absorption bands were present: 1410 and 1210 cm⁻¹, but they did not match the signature vibrations of either a surface $\equiv C - CF_3^{12}$ or $-CF = CF_2^{13}$ moiety. In fact, the spectrum was identical with that produced by CF₃C=CCF₃ adsorbed on Cu-(111) and annealed to 400 K, where the 1410 cm^{-1} band is, rather, attributed to the v_{CC} and the 1210 cm⁻¹ band is ascribed to the $v_{s}(CF_{3})$ mode. The large red-shift of the CC stretching mode indicates that the symmetric alkyne is strongly perturbed upon adsorption, leading to a reduced bond order of its C=C group.¹⁴ The strongly chemisorbed CF₃C=CCF₃ may adopt a $\mu - \eta^2, \eta^2$ binding geometry discovered in metal-alkyne complexes, in which the ligand is bonded to two metal centers, with the C-C axis perpendicular to the metal-metal axis as a tetrahedral form.¹⁵ In C1s XPS. we expected that the exact number of F atoms bonded to C atom for the surface-bound fluorocarbon species can be discerned because of a significant core-level shift exerted by the highly electronegative fluorine. Although only one type of C-F bonding environment, CF₃(C1s binding energy at 291.3 eV), was observed between 350 and 400 K for C₂F₅I/Cu(111), it was not obvious whether the spectra represent 2-butyne (end product) or ethylidyne (intermediate).

It is generally accepted that ethylidyne is the favored intermediate against vinyl on close-packed fcc(111) surfaces where $\equiv C-CH_3$ prefers to sit at the *threefold hollow site* by forming three bonds with the metal surface.¹⁶ If the generation of $CF_3C = CCF_3$ and the intermediacy of Cu=C-CF₃ on Cu(111) do correlate, we anticipate that the 425 K pathway will not occur on a more open surface devoid of threefold hollow sites, such as Cu(100). In this vein, we measured the TPR/D spectra by dosing C_2F_5I on Cu(100). As illustrated in Figure 2d, only one desorption state arises at 330 K, and $CF_3C \equiv CCF_3$ is indeed absent because of the lack of m/e 143 and 162 signals. Instead, CF₃CF=CFCF₃ accounts best for the relative peak intensities of m/e 181, 131, and 93.⁶ This observed end product suggests that $Cu-CF_2CF_3$ is susceptible to the α -F elimination step only once on Cu(100), yielding surface $=^{\alpha}CF$ -CF₃ species⁷ that couple to form a perfluoroalkene at lower temperatures.17 The surface-specific result should lend strong support to the α,α -fluoride elimination imperative for C₂F₅/Cu-(111). While the fate of \equiv C-CH₃ intermediate is high-temperature decomposition in conjunction with a surface carbon buildup, it might be hard to maintain the metal-carbon bond integrity for $\equiv C \ensuremath{\text{CF}}_3$ on a metal surface. The electronegative $\ensuremath{\text{CF}}_3$ group weakens the orbital overlap between the metal and α -carbon in Cu=CCF₃. Thus, on Cu(111) an unusual CC bond formation step becomes possible, $2Cu \equiv CCF_3 \rightarrow Cu \equiv Cu + CF_3C \equiv CCF_{3(ad)}$, reminiscent of a reverse metathesis-type reaction involving metal-metal multiple bonds to give alkylidyne complexes (Chauvin-like mechanism).¹⁸ This coupling process can be relatively facile; therefore, as successive α, α -fluoride elimination of Cu-CF₂CF₃ takes place, the resulting Cu=CCF₃ readily converts to a tightly surface-bound $(\mu - \eta^2, \eta^2)$ -C₄-alkyne (the only IR recognizable species). The overall reaction path is rate-limited by the product desorption step, following first-order kinetics (see the unchanged peak temperature with increasing exposure in Figure 1). The last puzzle about the pathway from Cu–CF=CF₂ to CF₃C=CCF₃ (Figure 2c, top) must be explained by the rapid isomerization from $Cu-CF=CF_2$ to Cu=

CCF₃ on Cu(111). This type of vinyl-to-ethylidyne rearrangement was observed on a (111) surface of Pd.¹⁹ Altogether, we propose the following mechanism:

$$\underbrace{ \begin{array}{c} C_2F_3I \\ Cu(111) \end{array}}_{Cu(111)} \longrightarrow \underbrace{ \begin{array}{c} CF_3 \\ CF_2 \\ I \\ Iow coverage \end{array}} \xrightarrow{>3255 \text{ K}} \underbrace{ \begin{array}{c} CF_3 \\ CF_3 \\ FF \\ 3-6id \text{ hollow sites} \end{array}}_{3-6id \text{ hollow sites}} \underbrace{ \begin{array}{c} CF_3 \\ F_3 \\ FF \\ FF \\ Iow \\ FF \\$$

Ethyl (-CH₂CH₃) on transition-metal surfaces is dominated by the H-elimination from the β -position.¹⁰ On the other hand, β -F elimination is favored by a semifluorinated ethyl (-CH2CF3) on Ag(111) to yield $CH_2 = CF_2$.²⁰ Here we have established a different pathway available for the perfluorinated ethyl $(-CF_2CF_3)$ where α -elimination prevails, and thus two C-F bonds adjacent to the surface are selectively activated. We believe this difference is initiated by the exceptionally labile α -CF bonds in the fluorocarbon group (CF₂R) bound to a metal center or surface (M), comprehensible by resonance such as $M-CF_2R \leftrightarrow M^+=CFR + F^-$, or the back-donation of metal $d\pi$ electrons into the C-F antibonding orbital.²¹ The removal of the second F atom from the β -carbon $(M=\alpha CF-\beta CF_3)$ is usually hindered by the relative difficulty in breaking a C-F bond for compounds with two or more F atoms attached to the same carbon.²² Further, on Cu(111) the available threefold hollow sites are beneficial to the consecutive α -F abstraction to afford trifluoroethylidyne, resulting in the final coupling product. We foresee that pathways involving α -elimination steps may prove to be quite general for fluorine-substituted alkyl groups bound to metal surfaces.

Acknowledgment. We thank the financial support from the National Science Council of the Republic of China under Contract No. 92-2113-M-110-017 and 92-2816-M-110-0002-6.

References

- (1) Dolbier, W. R., Jr. Chem. Rev. 1996, 96, 1557. Kiplinger, J. L.; Richmond, T. G.; Osterberg, C. Chem. Rev. 1994, 94, (2)
- 373.
- (3) Burton, D. J.; Yang, Z.-Y. Tetrahedron 1992, 48, 189.
- (4) Zaera, F. Acc. Chem. Res. 1992, 25, 260.
 (5) Sugawara, K.; Sun, W.; Wach, Th.; Wanner, J. Ber. Bunsen-Ges. Phys. Chem. 1995, 99, 1357
- (6) The spectrum was checked by backfilling the chamber with pure C_4F_8 gas.
- (7) Borovkov, V. Y.; Lonyi, F.; Kovalchuk, V. I.; d'Itri, J. L. J. Phys. Chem. B 2000, 104, 5603
- Wu, G.; Stacchiola, D.; Kaltchev, M.; Tysoe, W. T. J. Am. Chem. Soc. (8)2000, 122, 8232
- (9) The major fragment of fluorocarbon radicals usually results from the loss of one fluorine atom during electron-impact ionization. For example, see: Jensen, M. B.; Thiel, P. A. J. Am. Chem. Soc. **1995**, *117*, 438.
- (10) For an excellent review, see: Zaera, F. Prog. Surf. Sci. 2001, 69, 1.
 (11) Burton, D. J.; Yang, Z.-Y.; Morken, P. A. Tetrahedron 1994, 50, 2993.
- (12) The fingerprinting bands of \equiv CCF₃ are at 1160–1165 cm⁻¹ v_{as} (CF₃) and 1218–1228 cm⁻¹ v_s (CF₃). For details, see ref 7. (13) The RAIR spectra of CF₂=CFI/Cu(111) below 400 K exhibit bands at
- 1625 ($\nu_{C=C}$), 1285 ($\nu_{as} CF_2$), and 985 cm⁻¹ ($\nu_s CF_2$), diagnostic of a stable vinylic species trapped on the surface. For assignments, see: Stafford, S. .; Stone, F. G. A. Spectrochim. Acta 1961, 17, 412.
- (14) Chesters, M. A.; McCash, E. M. J. Electron Spectrosc. Relat. Phenom. 1987, 44, 99.
- (15) Ros, R.; Tassan, A.; Roulet, R.; Laurenczy, G.; Duprez, V.; Schenk, K. . Chem. Soc., Dalton Trans. 2002, 3565.
- (16) Pallassana, V.; Neurock, M.; Lusvardi, V. S.; Kragten, D. D.; van Santen, R. A. J. Phys. Chem. B 2002, 106, 1656 and references therein.
- (17) Parallel reaction results were observed in the pyrolysis of a (C₂F₅)₂Fe-(CO)₄ complex. For details, see: King, R. B.; Stafford, S. L.; Treichel, P. M.; Stone, F. G. A. J. Am. Chem. Soc. 1961, 83, 3604.
- (18) Schrock, R. R.; Listemann, M. L.; Sturgeoff, L. G. J. Am. Chem. Soc. 1982. 104. 4291.
- (19) Azad, S.; Kaltchev, M.; Stacchiola, D.; Wu, G.; Tysoe, W. T. J. Phys. Chem. B 2000, 104, 3107.
- (20) Paul, A.; Gellman, A. J. *Langmuir* 1995, *11*, 4433.
 (21) Brothers, P. J.; Roper, W. R. *Chem. Rev.* 1988, 88, 1293.
 (22) For example, D(CH₃CH₂-F) is 105.5 kcal/mol, while D(CH₃CF₂-F) is 124.8 kcal/mol. See: Witt, S. D.; Wu, E.-C.; Loh, K.-L.; Tang, Y.-N. J. Catal. 1981, 71, 270.

JA047831F